

## Abstract

### Method for fabricating a trench isolation structure

- 5 A method for fabricating a trench isolation structure,  
including forming a mask on a substrate, forming at least  
one trench in the substrate with the mask, carrying out  
selective deposition of a first insulation material to at  
least partially fill the at least one trench in the  
10 substrate with the insulation material in the presence of  
the mask, and applying a second insulation material over  
the entire surface of the structure in order to fill the  
at least one trench in the substrate at least up to the  
top side of the mask.

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